

IN THE CLAIMS:

~~Please amend claims 1, 3, 4 and 5 as follows:~~

B3 1. (Currently Amended) A method of manufacturing a metallic film consisting essentially of a giant single crystal grains, ~~comprising~~consisting essentially of the steps of:

a first step of depositing the metallic film directly on a substrate at an atmosphere of an inert gas and a specified additive gas to change a surface energy, grain boundary energy, or internal strain energy of the metallic film; and

a second step of annealing the resultant of the first step at a temperature suitable for carrying out a grain growth of the metallic film containing the additive gas.

2. (Original) In the method as claimed in claim 1, the change of the surface energy, grain boundary energy, or internal strain energy of the metallic film is performed by incorporating the additive gas to the metallic film, or production of a compound between the additive gas and the metallic film.

3. (Currently Amended) The method as claimed in claim 1, wherein the deposition of the metallic film is performed by ~~any one a process~~ selected from the group consisting of a DC/RF magnetron sputtering, DC/RF sputtering, metal organic chemical vapor deposition, vacuum evaraporaion, laser ablation, ionized beam deposition, and electroplating.

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4. (Currently Amended) The method as claimed in claim 1, wherein the additive gas is ~~any one~~ selected from ~~the group consisting of~~ O₂, N₂+O₂, N₂O, Cl, and N₂.
5. (Currently Amended) The method as claimed in claim 1, wherein the metallic film is ~~any one~~ selected from ~~the group consisting of~~ Pt, Au, Cu, Al, Ni, Ag, Ir, Pd, Ti, Ru, Ta, W, Os, and Rh.
6. (Original) A metallic film consisting of giant single crystal grains having a grain size whose ratio of thickness to an average grain size of the film is above 50 produced according to any one of preceding claims 1 to 5.
7. (New) The method of claim 1 comprising the step of growing the metallic layer so that the giant single crystal grain has a grain size with a ratio of thickness to an average grain size of the metallic film of more than 50 to 1.
8. (New) The method of claim 1 comprising the step of growing the metallic layer so that the giant single crystal grain has a grain size with a ratio of thickness to an average grain size of the metallic film of more than 1000 to 1.

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9. (New) A method of manufacturing a metallic film comprising a single crystal grain comprising the steps of:

depositing a metallic film on a substrate so that the single crystal grain has a grain size with a ratio of thickness to an average grain size of the metallic film of over 50 to 1, and annealing the film.

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